

114	17	((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:57
		coating)) and (surface near roughness)) and (vapor near (deposition	US-PGPUB;	
		deposited deposit depositing))) and (alkylchlorosilane	EPO; JPO;	
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2	DERWENT	
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
115		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
	103	(ch?sub.3 near si near cl?sub.3))	LICDAT.	2002/12/27 10 16
113	103	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 10:16
		coating)) and (surface near roughness)) and (vapor near (deposition	US-PGPUB; EPO; JPO;	
		deposited deposit deposition (deposition)))	DERWENT	
116	99	(((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and	USPAT;	2002/12/27 10:17
110		(((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	US-PGPUB;	2002/12/27 10.17
		coating)) and (surface near roughness)) and (vapor near (deposition	EPO; JPO;	İ
		deposited deposit depositing)))) not ((((sicl4 sicl?sub.4 (silicon near	DERWENT	
		tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!))		
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2		
		sio?sub.2) same (layer coating)) same (humidity rh))) (((sicl4 sicl?sub.4		
		(silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!))		
		((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same		
		((humidity) rh!)) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same		
		(vapor gas)) same ((relative near humifity) rh!))) (428/426,446,447.ccls.		
		and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same		
		(layer coating)) same haze)) ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2)) and (root near mean near square near surface near		
		roughness)) ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)		
		same (layer coating)) and (root near mean near square near surface near		
		roughness)) (((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2))		
		and (root near mean near square near surface near roughness)) not		
		((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
		coating)) and (root near mean near square near surface near roughness))) ((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
		coating)) and (surface near roughness)) and (vapor near (deposition		
		deposited deposit depositing))) and (alkylchlorosilane		
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2		
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
		(ch?sub.3 near si near cl?sub.3))))		
-	276323	polysiloxane organopolysiloxane polyorganosiloxane	USPAT;	2002/01/04 06:57
		polydiorganosiloxane diorganopolysiloxane silicone	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	6	((USPAT	2002/12/19 12:24
		("6416816") or ("6245387")).PN.		
-	0	wo-0025938-\$.did.	USPAT;	2002/12/19 12:24
			US-PGPUB;	
			EPO; JPO;	
		00005000 # 111	DERWENT	
-	0	wo-00025938-\$.did.	USPAT;	2002/12/19 12:24
			US-PGPUB;	
			EPO; JPO;	
		25020 € 4:4	DERWENT	0000404040
-	0	wo-25938-\$.did.	USPAT;	2002/12/19 12:31
			US-PGPUB;	
			EPO; JPO;	
_	0	wo-025938-\$.did.	DERWENT	2002/12/10 12 21
_		₩U=UZJJJO*\$.UIU.	USPAT;	2002/12/19 12:31
-			US-PGPUB;	
-			-	
-			EPO; JPO;	
-	0	wo-00025938 an	EPO; JPO; DERWENT	2002/12/10 12:22
-	0	wo-00025938.ap.	EPO; JPO; DERWENT USPAT;	2002/12/19 12:32
- -	0	wo-00025938.ap.	EPO; JPO; DERWENT	2002/12/19 12:32

•	0	2000wo-0025938.ap.	USPAT;	2002/12/19 12:33
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	131	"25938"	USPAT;	2002/12/19 12:36
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	7761	428/426,446,447.ccls.	USPAT;	2002/12/19 12:37
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	161140	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)	USPAT;	2002/12/19 12:45
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1327	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:49
		and haze	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	9620	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:49
		and (humidity rh)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	145	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2	USPAT;	2002/12/19 12:50
		sio?sub.2) same (layer coating)) and haze)	US-PGPUB;	
		, , () , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT	
_	352	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2	USPAT;	2002/12/27 08:02
:		sio?sub.2) same (layer coating)) and (humidity rh))	US-PGPUB;	2002/12/2/ 00:02
		(EPO; JPO;	
			DERWENT	
_	47	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:47
		and (root near mean near square near surface near roughness)	US-PGPUB;	2002/12/19 12.47
		and (coor near mean near square near confinence)	EPO; JPO;	
			DERWENT	
-	256721	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/19 12:46
		coating)	US-PGPUB;	2002/12/19 12:10
			EPO; JPO;	
			DERWENT	
-	7037	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:28
	, , , , ,	coating)) and (surface near roughness)	US-PGPUB;	2002/12/27 07.20
			EPO; JPO;	
			DERWENT	
_	2839	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/19 12:49
	2037	coating)) and haze	US-PGPUB;	20021211712.77
			EPO; JPO;	
			DERWENT	
_	19608	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 07:55
	1,000	coating)) and (humidity rh)	US-PGPUB;	2002/12/2/ 01.33
			EPO; JPO;	
			DERWENT	
_	193	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:50
	1/3	siO2 sio?sub.2) same (layer coating)) and (surface near roughness))	US-PGPUB;	2002/12/17 12.30
		0.02 5.0: 500.2) 5ame (1ayer coaring)) and (5amace near roughness))		
			EPO; JPO;	
_	258	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	DERWENT	2002/12/27 00:20
	230	siO2 sio?sub.2) same (layer coating)) and haze)	USPAT;	2002/12/27 08:20
		5102 510:500.2) Same (rayer coating)) and maze)	US-PGPUB;	
			EPO; JPO;	
_	605	428/426 446 447 ools and ((((silicon noon (district:it-)) -:ii 'O	DERWENT	2002/12/10 12 52
-	605	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:50
		siO2 sio?sub.2) same (layer coating)) and (humidity rh))	US-PGPUB;	
			EPO; JPO;	
L			DERWENT	

16	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:50
	siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and	US-PGPUB:	2002/12/17 12:50
	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	EPO; JPO;	
	siO2 sio?sub.2) same (layer coating)) and haze)) and	DERWENT	
	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
	siO2 sio?sub.2) same (layer coating)) and (humidity rh)))	1	
61	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:21
	coating)) and (root near mean near square near surface near roughness)	US-PGPUB;	
		EPO; JPO;	
1.5	(//20//20 / 4/5 / 1/2 - 4 / / / / / / / / / / / / / / / / / /	DERWENT	
15	((428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:51
	siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and	US-PGPUB;	
	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	EPO; JPO;	
	siO2 sio?sub.2) same (layer coating)) and haze)) and	DERWENT	
	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
	siO2 sio?sub.2) same (layer coating)) and (humidity rh)))) not ((((silicon near (dioxide exide)) silica siO2 sio?sub.2))		
-	near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))		